## AbstractID:8485Title:Ana lysisofElec tronCuto utFa ctorMe asurements

Purpose:Tocompar eele ctroncu tout factor(COF) m easuredwi thvariousdos imetersf ordif ferentcones izes.

**Method and Materials:** The COFs for various electron fi elds were measure dona Var ian-2300 EX linear accelerator at 6,9, 12,16 and 20 MeV. At himble ion chamber, plane parallel cham ber, thermolum inescent dosimeters (TLDs), E DR fi lm, X Omat-V (XV) film, Ga fChromic fi lmand Thomson -Nielsenm osfets were used to measure COFs. E achdetector was placed along the beam's central axisat 10 0 cm from theso urce. Measurem ents werem ade insolid water at dmax for 6x6, 10x10 and 20x20 conesize swith circular cutouts. The thimble chamber was used as the standard to compare COF measurements. The raw measurements made with the two chambers and the diode swere used to determ in the COFs. Films were analyzed with RITso ftware and TLDs were read the next day to de termine COFs.

**Results:** Measurements forthe10 x10 and20x20conesizesagreedwit hin3.5% betweenallt hedosim etersandt he thimblechamber. Measurements madeforthe6x6con ea ndcutout weremoret han3.5% fromt hosemadewith thethimblechamber. Therewasbetter agreementfor COFmea surementsbetweenth em osfets,TLDs, EDRfilm andXV film.

**Conclusions:** Thisstudytak esalook at thevari ous dosimetersavai lable atth eclini ct hatcan be usedf ordetermi ningelectroncutout factors.Form ostcut outsizes, ion ization chambers,mosfets,TLDs,EDR,XVandGafChro for alle lectron energies.For small fiel dsi zes,th euseofTLDs,mosfets,andfilmcangivemor eaccurateCOFs.